

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Keiko CHIBA et al.

Application No.: Divisional of Application No.  
09/970,826, filed October 5, 2001

Filed: December 17, 2003

For: REFLECTION TYPE MASK (As Amended)

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: Previous Examiner: H. K. Song  
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: Previous Group Art Unit: 2882  
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): December 17, 2003**Mail Stop Patent Application**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Sir:

Prior to examination on the merits, please amend the above-identified application as follows:

IN THE TITLE:

Please cancel the current title and insert the following:

~~X-RAY MASK, AND EXPOSURE APPARATUS AND METHOD USING THE SAME~~

-- REFLECTION TYPE MASK --.